

Joint Session of Optics Contamination Workshop and Resist TWG Meeting Agenda

October 19, 2006 Barcelona, Spain

World Trade Center, Ground Floor, Port Vell 2

8:00	Breakfast	All
8:30	Welcome & Introductions	K. Dean
8:40	Measurements of HC Levels in Stepper Vacuums	A. Keen, BOC Edwards
8:55	Novel method to quantify resist outgassing induced contamination rates	B. Wolschrijn, TNO
9:10	Acceptable photoresist outgassing	T. Aoki, Nikon
9:25	Witness plate testing: The convergence of resist outgassing and optics contamination	G. Denbeaux, U. at Albany
9:40	Contamination removal study	T. Watanabe, U. of Hyogo
9:55	Resist Outgassing Round Robin	I. Nishiyama, ASET
10:10	Discussion	
10:25	Break	
10:45-12:30	IEUVI Resist TWG Agenda next page Room CIC 1, Ground Floor	

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10:25	Break	
10:45	Regional Updates; ASET, IMEC, More Moore, SEMATECH (10 minutes each)	Nishiyama (ASET), Goethals (IMEC), Tedesco (CEA/LETI), Dean (SEMATECH)
11:30	Dose Calibrations, Resist Funding Gap Analysis, Specification Roadmap	Dean
12:00	Resist research based using small EUV exposure tool	Tagawa (University of Osaka)
12:15	Wrap up, Topics for Next Meeting	Tedesco
12:30	Lunch Grand Marina Hotel, Maritina Room	All
13:30	Adjourn	